	Type	L #	Hits	Search Text	DBs
1	BRS	L1	1	(emitter near3 pad) near25	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
2	BRS ·	L2			US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
3	BRS	L3	1726	(emitter) near25 (intrinsic near3 base)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
4	BRS	L4		3 and (land\$3 near pad)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B

	Type	L#	Hits	Search Text	DBs
5	BRS	L5		(emitter) near25 (intrinsic near3 base) near25 (land\$3	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
6	BRS	L6		(emitter) near25 (intrinsic near3 base) same (land\$3 near5 pad)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
7	BRS	L7		(emitter) near25 (intrinsic near3 base) and (land\$3	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
8	BŖŚ	L8	7	(intrinsic near3 base) and	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
9	BRS	L9	61	(intrinsic near3 base) and (emitter near5 pad)	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
10	BRS	L10	2	"5541121".pn.	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B
11	BRS	L11	2	"5506157".pn.	US- PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TD B

	U	1	Document ID	Title
1		ļ	US 20050048735 A1	BIPOLAR TRANSISTOR HAVING RAISED EXTRINSIC BASE WITH SELECTABLE SELF-ALIGNMENT AND METHODS OF FORMING SAME
2			US 20040262713 A1	High fT and fmax Bipolar Transistor and Method of Making Same
3			US 20040224461 A1	Method to fabricate high- performance NPN transistors in a BiCMOS process
4			US 20040222497 A1	METHOD TO FABRICATE HIGH- PERFORMANCE NPN TRANSISTORS IN A BICMOS PROCESS
5			US 6869852 B1	Self-aligned raised extrinsic base bipolar transistor structure and method
6			US 6809024 B1	Method to fabricate high- performance NPN transistors in a BiCMOS process